

Title (en)

PHOTOMASK WITH ELECTROSTATIC DISCHARGE PROTECTION

Title (de)

FOTOMASKE MIT SCHUTZ GEGEN ELEKTROSTATISCHE ENTLADUNG

Title (fr)

PHOTOMASQUE À PROTECTION CONTRE LES DÉCHARGES ÉLECTROSTATIQUES

Publication

**EP 3850431 A1 20210721 (EN)**

Application

**EP 19909773 A 20190117**

Priority

CN 2019072122 W 20190117

Abstract (en)

[origin: US2020233298A1] The present invention provides a photomask including a substrate, a circuit pattern on the substrate, an electrostatic discharge (ESD) ring on the substrate and an ESD line on the substrate. The ESD structure surrounds the circuit pattern. The ESD line extends between an edge of the substrate and the ESD structure, in which the ESD line includes an edge portion extending beyond an end of an edge of the ESD structure, and the edge portion of the ESD line includes at least one comb-shaped structure.

IPC 8 full level

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CPC (source: EP KR US)

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